

L Number	Hits	Search Text	DB	Time stamp
-	99	spin near5 coat\$3 and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 14:51
-	11	(spin near5 coat\$3) same buffer and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 14:35
-	75	(spin near5 coat\$3) and 117/\$4.ccls. and (anneal\$3 or rapid adj thermal or rta or ptp or rtp or heat adj treat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 15:00
-	45	(sol\$1gel or "sol gel") and 117/\$4.ccls. and (anneal\$3 or rapid adj thermal or rta or ptp or rtp or heat adj treat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 14:44
-	77	spin near5 coat\$3 and (nitrogen or nitride) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 14:52
-	15	spin near5 coat\$3 same (nitrogen or nitride) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 14:59
-	120	(spin near5 coat\$3) and (anneal\$3 or rapid adj thermal or rta or ptp or rtp or heat adj treat\$4) and "III-V"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 15:14
-	12	(spin near5 coat\$3) same "III-V" and (anneal\$3 or rapid adj thermal or rta or ptp or rtp or heat adj treat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 15:17
-	6	("III-V" same buffer) and (pn adj junction) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 15:42
-	82	("III-V" same buffer) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 16:04
-	6	("III-V" same buffer) and 117/\$4.ccls. and pn	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 15:46
-	51	("III-V" same buffer) and pn	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 15:46
-	14	spin adj coat\$3 adj cycle	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 15:52

-	82	"III-V" and pn and 117/\$4.ccls. and (process or method)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 16:05
-	6	spin adj coat\$3 same (mgo or alo ro magnesium adj oxide or zinc adj oxide or aluminum adj oxide) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 16:15
-	8	spin adj coat\$3 same (mgo or alo ro magnesium adj oxide or zinc adj oxide or aluminum adj oxide) and "III-V"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 16:27
-	138	(ammonia or "nh.sub.3") same reducing adj atmosphere same (anneal\$3 or rapid adj thermal or rta or rtp or ptp or heat adj treat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 16:44
-	18	(nitrogen) same (plasma or radical or atomic) same reducing adj atmosphere same (anneal\$3 or rapid adj thermal or rta or rtp or ptp or heat adj treat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 16:51
-	86	(nitrogen) same (plasma or radical or atomic) same reducing adj atmosphere	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 16:56
-	5	(nitrogen) same (radical) same reducing adj atmosphere	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 17:05
-	6	(atomic near5 nitrogen) same reducing adj atmosphere	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 16:57
-	11	(nitrogen) and 117/\$4.ccls. and cap and annealing and activation	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 17:05
-	24	(spin near5 coat\$3) and ("III-V" or gan or aln or sic) and (anneal\$3 or rapid adj thermal or rta or ptp or rtp or heat adj treat\$4) and (mgo or zno or magnesium adj oxide or aluminum adj oxide or zinc adj oxide) same spin	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 18:11
-	78	(spin near5 coat\$3) and ("III-V" or gan or aln or sic) and (anneal\$3 or rapid adj thermal or rta or ptp or rtp or heat adj treat\$4) same (oxidiz\$3 or "o.sub.2" or oxygen) and (mgo or zno or magnesium adj oxide or aluminum adj oxide or zinc adj oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/13 18:12
-	11	(spin same coat\$3) same (mgo or alo or zno or zinc or magnesium or aluminum) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/10 15:46
-	19	buffer same (mgo or alo or zno or magnesium adj oxide or aluminum adj oxide or zinc adj oxide) and "III-V" and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/10 15:55

-	33	(anneal\$3 or heat adj treat\$4 or rapid adj thermal or rta or rtp or ptp) same spin and ("III-V" or Gan or gallium or nitride or oxide) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 10:47
-	10	PZT same buffer same "III-V"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 10:49
-	31	perovskites same buffer same "III-V"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 10:52
-	15	(zinc or aluminum or magnesium) same oxide same buffer same "III-V"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 10:58
-	90	oxide same buffer same "III-V"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 11:12
-	38	oxide same buffer and "III-V" and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 11:51
-	16	sol\$1gel and 117/\$4.ccls. and nitride	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 13:12
-	33	((anneal\$3 or heat adj treat\$4 or rapid adj thermal or rta or rtp or ptp) and spin near3 coat\$4 same (oxide or aluminum or magnesium or zinc)) and "III-V"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 13:24
-	77	(anneal\$3 or heat adj treat\$4 or rapid adj thermal or rta or rtp or ptp) same spin near3 coat\$4 same oxide and nitride same (gallium or aluminum)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 13:41
-	58	(anneal\$3 or heat adj treat\$4 or rapid adj thermal or rta or rtp or ptp) same spin near3 coat\$4 same (aluminum adj oxide or zinc adj oxide or magnesium adj oxide or metal adj oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 13:47
-	15	(anneal\$3 or heat adj treat\$4 or rapid adj thermal or rta or rtp or ptp) same spin near3 coat\$4 same (aluminum adj oxide or zinc adj oxide or magnesium adj oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 17:27
-	3	(anneal\$3 or heat adj treat\$4 or rapid adj thermal or rta or rtp or ptp) same spin near3 coat\$4 and oxide same buffer and "III-v"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 14:33
-	79	(anneal\$3 or heat adj treat\$4 or rapid adj thermal or rta or rtp or ptp) same spin near3 coat\$4 and oxide same buffer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 14:36
-	35	buffer same oxide same ("III-V" or nitride) same spin	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 14:47

-	145	buffer same oxide same spin	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 14:47
-	62	aln same buffer same "III-V"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 14:57
-	115	silicon adj substrate same (silicon adj carbide or sic) adj layer and (117/\$4.ccls. or 438/\$4.ccls. or 257/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 16:46
-	86	silicon adj substrate same (zinc adj oxide or zno) and (117/\$4.ccls. or 438/\$4.ccls. or 257/\$4.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 16:51
-	16	silicon adj substrate same (zinc adj oxide or zno) and "iii-v"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 16:52
-	68	(zno or zinc) same (silicon or si) adj substrate same buffer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 17:12
-	15	spin near3 coat\$4 same (aluminum adj oxide or zinc adj oxide or magnesium adj oxide) same (anneal\$3 or heat adj treat\$4 or rapid adj thermal or rta or rtp or ptp)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 18:13
-	31	(anneal\$3 or heat adj treat\$4 or rapid adj thermal or rta or rtp or ptp) same (h2o or "h.sub2.o") same oxygen	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/15 18:24
-	24	((ammonia or "nh.sub.3") same reducing same (gas\$3 or vapor)) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/16 11:40
-	93	(ammonia or "nh.sub.3") same reducing near2 (gas\$3 or vapor) same (heat adj treat\$4 or anneal\$4 or rapid adj thermal or rta or ptp or rtp)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/16 11:48
-	15	((ammonia or "nh.sub.3") same reducing near2 (gas\$3 or vapor) same (heat adj treat\$4 or anneal\$4 or rapid adj thermal or rta or ptp or rtp)) and 438/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/16 13:19
-	137	(nitrogen or "n.sub.2") near3 (atomic or radical or plasma) same reduc\$4 near3 (gas\$3 or atmosphere or vapor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/16 15:11
-	48	(nitrogen or "n.sub.2") near3 (atomic or radical or plasma) same reduc\$4 near3 (gas\$3 or atmosphere or vapor) and semiconductor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/10/16 15:28